

# ISO/TS 21383:2021 (E)

## Microbeam analysis — Scanning electron microscopy — Qualification of the scanning electron microscope for quantitative measurements

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### Contents

|       |   |
|-------|---|
|       | Foreword  |
|       | Introduction  |
| 1     | Scope   |
| 2     | Normative references  |
| 3     | Terms and definitions   |
| 4     | Symbols and abbreviated terms   |
| 5     | General principles  |
| 5.1   | Condition setting   |
| 5.2   | Contrast/brightness setting   |
| 5.3   | Sample preparation  |
| 6     | Measurement of image sharpness  |
| 7     | Measurement of drift and drift-related distortions (imaging repeatability)                          |
| 7.1   | Measurement of image drifts within specified time intervals.  |
| 7.1.1 | One-minute drift measurement  |
| 7.1.2 | Ten-minute drift measurement  |
| 7.1.3 | One-hour drift measurement  |
| 7.1.4 | Long-term larger than one-hour drift measurement  |
| 7.2   | Evaluation of the drift and the drift-related distortions by using image overlay                    |
| 7.3   | Evaluation of the drift and the drift-related distortions by using cross-correlation function (CCF) |
| 7.3.1 | Measurement of the drifts by using the CCF  |
| 7.3.2 | Measurement of the distortions by using the CCF   |
| 8     | Measurement of electron-beam-induced contamination  |
| 8.1   | Cleaning of the sample surface  |
| 8.2   | Cleaning of the inner surfaces of the sample chamber  |
| 8.3   | Measurement method of the contamination   |
| 8.3.1 | Measurement of the height of the contamination growth   |
| 8.3.2 | Measurement of relative carbon concentration of the contamination by the X-ray analysis             |
| 8.3.3 | Measurement of the surface contamination by the change of SEM signal intensities                    |
| 9     | Measurement of the image magnification and linearity  |
| 9.1   | Measurement of the image magnification  |
| 9.2   | Measurement of the image linearity  |
| 10    | Measurement of background noise   |
| 10.1  | Evaluation methods by using noise profiles and processed images                                     |
| 10.2  | Evaluation methods by calculating numerical image properties  |
| 11    | Measurement of the primary electron beam current  |
| 11.1  | Ten-minute primary electron beam current measurement  |
| 11.2  | Long-term primary electron beam current measurement   |
| 12    | Reporting Form  |

**Annex A (informative) Measurement of image sharpness**

**Annex B (informative) Measurement of image drift and distortions caused by unintended motions**

- B.1 Overview**
- B.2 Measurement of image drifts within specified time intervals**
  - B.2.1 One-minute drift measurement**
  - B.2.2 Ten-minute drift measurement**
  - B.2.3 One-hour drift measurement**
  - B.2.4 Long term (ten-hour) drift measurement**
- B.3 Measurement of image drift and the drift-related distortions by using image overlay**
- B.4 Measurement of the distortions caused by high-frequency motions or stage vibration**
- B.5 Measurement of the drifts and drift-compensated imaging**
- B.6 Measurement of image drifts and distortions by the cross-correlation method**
  - B.6.1 Measurement of the drifts by using the CCF**
  - B.6.2 Measurement of the distortions by using the CCF**

**Annex C (informative) Measurement of electron beam-induced contamination**

- C.1 Overview**
- C.2 Contamination growths for the unclean sample and the unclean instrument**
- C.3 The effect of the plasma cleaning and the electron beam shower**
- C.4 The quantitative treatments of the image signal**

**Annex D (informative) Measurement of the image magnification and linearity**

- D.1 Overview**
- D.2 Calibration of the image magnification**

**Annex E (informative) Measurement of the primary electron beam current**

- E.1 Overview**
- E.2 Electron beam current stabilities for various landing energy**
- E.3 The handcraft of the Faraday cup and the usage**

Page count: 59